

**INFORMATION DISCLOSURE STATEMENT**

Applicant : Masuda et al.  
App. No : 10/568,126  
Filed : February 14, 2006  
For : POSITIVE PHOTORESIST  
COMPOSITION AND RESIST  
PATTERN FORMATION  
Examiner : John S. Y. Chu  
Art Unit : 1752

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 10 references to be considered by the Examiner. Also enclosed are 6 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement.

This Information Disclosure Statement is being filed before the mailing date of a final action and before the mailing date of a Notice of Allowance.

CERTIFICATION UNDER 37 C.F.R. § 1.97(e)(1)

I hereby certify that each item of information contained in this Statement was first cited in a communication from a foreign Patent Office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement.

Thus, no fee is required as set forth in 37 C.F.R. § 1.97(c).

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: December 14, 2006

By: 

Neil S. Bartfeld, Ph.D.  
Registration No. 39,901  
Agent of Record  
Customer No. 20,995  
(619) 235-8550

<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  <i>(Multiple sheets used when necessary)</i>	Application No.	10/568,126	
	Filing Date	February 14, 2006	
	First Named Inventor	Yasuo Masuda	
	Art Unit	1752	
(Multiple sheets used when necessary)		Examiner	John S. Y. Chu
SHEET 1 OF 1		Attorney Docket No.	SHIGA7.045APC

### U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
	1	6,210,855 B1	04-03-2001	Ueda et al.	
	2	6,384,103 B1	05-07-2002	Arano et al.	
	3	6,437,058 A2	08-20-2002	Furihata et al.	
	4	6,790,581 B2	09-14-2004	Kato et al.	

### FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T <sup>1</sup>
	5	JP 10-148942	06-02-1998	Tokyo Ohka Kogyo Co. Ltd.		✓
	6	JP 11-223937	08-17-1999	Fuji Film Olin KK.		✓
	7	JP 62-262043	11-14-1987	Tokyo Ohka Kogyo Co. Ltd.		Abstract
	8	JP 2000-181055	06-30-2000	Tokyo Ohka Kogyo Co. Ltd.		✓
	9	JP 2000-231200	08-22-2000	Mitsubishi Chemicals Corp.		✓

### NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>1</sup>
	10	Office Action dated October 31, 2006 for counterpart Japanese Patent Application No. 2003-325953.	

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Examiner Signature	Date Considered
<p><b>*Examiner:</b> Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>	

T<sup>1</sup> - Place a check mark in this area when an English language Translation is attached.